AMENDMENT TRANSMITTAL LETTER (Large Entity) Applicant(s): Shields & Ko						Docket No. D730	
2081825		g Date /9/98	Examiner T. Nguyen			Group Art Unit 2813	
Invertion: EASACRIFICIAL TIN ARC LAYER FOR INCREASED PAD ETCH THROUGHPUT							RE(NO) TC 2805
TO THE ASSISTANT COMMISSIONER FOR PATENTS: Transmitted herewith is an amendment in the above-identified application. The fee has been calculated and is transmitted as shown below.							RECEIVED NOV 30 2000 2805 MA!L ROOM
CLAIMS AS AMENDED							
	CLAIMS REMAINING		HIGHEST#	NUMBER EXTRA	RATE	<u>. </u>	ADDITIONAL
	AFTER AM	ENDMENT	PREV. PAID FOR				FEE
TOTAL CLAIMS	4	•	20 =		-	8.00	\$0.00
INDEP. CLAIMS	1	-	3 =	0	× \$8	0.00	\$0.00
Multiple Dependent Claims (check if applicable)							\$0.00
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT \$0.00							
No additional fee is required for amendment. Please charge Deposit Account No. in the amount of A uplicate copy of this sheet is enclosed. A clack in the amount of to cover the filing fee is enclosed. The Commissioner is hereby authorized to charge payment of the following fees associated with the communication or credit any overpayment to Deposit Account No. 01-0365 A duplicate copy of this sheet is enclosed. Any additional filing fees required under 37 C.F.R. 1.16. Any patent application processing fees under 37 CFR 1.17. Dated: 11/17/00 H. Donald Nelson, Reg. No. 28,980							
	8	,					
11/ class Assis					I certify that this document and fee is being deposited on 11/17/00 with the U.S. Postal Service as first class mail under 37 C.F.R. 1.8 and is addressed to the Assistant Commissioner for Patents, Washington, D.C. 20231. Signature of Person Mailing Correspondence H. Donald Nelson		
cc: QAVIAGE					Typed or Printed Name of Person Mailing Correspondence		

Typed or Printed Name of Person Mailing Correspondence





IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants:

Shields & Ko

Assignee:

Advanced Micro Devices, Inc.

Title:

A SACRIFICIAL TIN ARC LAYER FOR INCREASED PAD ETCH

THROUGHPUT

Serial No.:

09/208,325

Filed: 12/9/98

Examiner:

T. Nguyen

Group Art Unit: 2813

Attorney Docket No.: D730

Anthem, Arizona

November 17, 2000

COMMISSIONER OF PATENTS AND TRADEMARKS Washington, D.C. 20231

AMENDMENT AFTER FINAL

Sir:

In response to the Examiner's Final Office Action of 9/14/00, please amend the above-cited application as follows.

In the Claims

Please amend the claims as follows. In accordance with the new rules, if a claim is amended, a marked up version of the claim is included along with a clean version and, in addition, a clean set of all the claims is included.

Please amend Claims 1 & 5 as follows:

1. (Twice amended) A method of manufacturing a semiconductor device, wherein the method comprises:

forming a final layer of metal on a layer of interlayer dielectric in the semiconductor device; forming a layer of TiN on the final layer of metal;

forming a first layer of photoresist on the layer of TiN;

patterning and developing the first layer of photoresist exposing portions of the layer of TiN; etching holes in the layer of TiN and the final layer of metal exposing portions of the

interlayer dielectric, wherein metal structures are formed;

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Serial No. 09/208,325 11/17/00